

ELEC-E9210 Organic Electronics: Materials,
Devices & Applications

Organic Field-Effect Transistors II



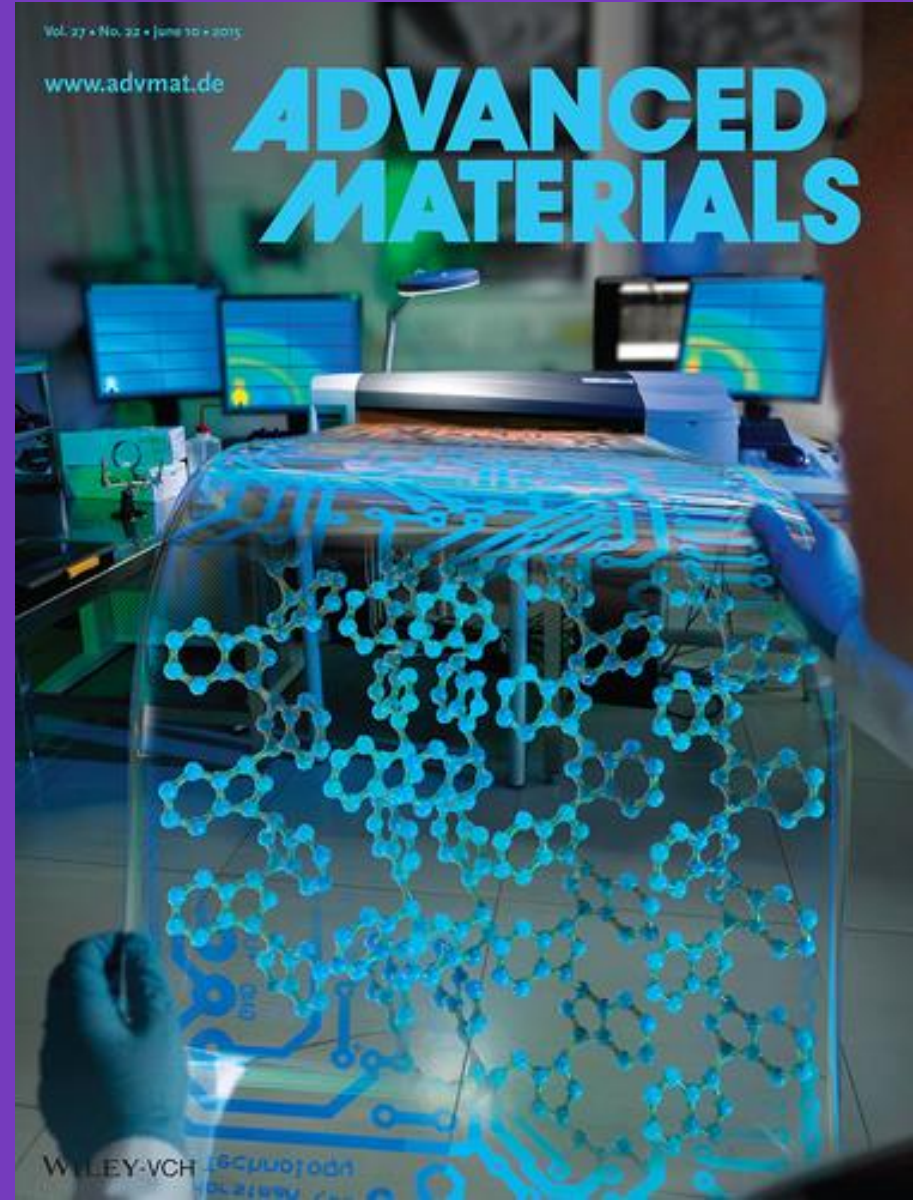
Aalto University
School of Electrical
Engineering

organicelectronics.aalto.fi

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ADVANCED MATERIALS



WILEY-VCH

Today's Class

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Previously

- basic *working principle* of organic *field-effect transistor* and main features

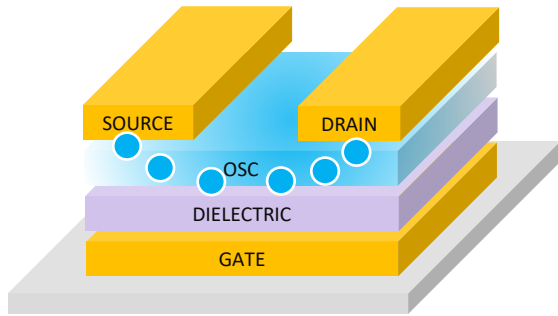
Today's class

- *building blocks* of organic transistor and how to engineer those to improve



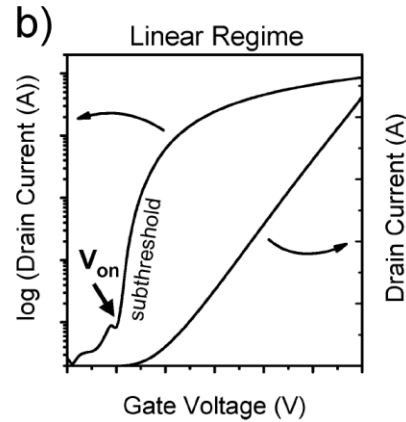
OFET in Brief

3

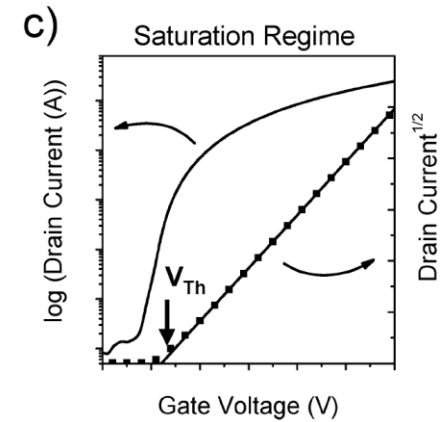


Field-Effect Transport (FET)

- 3 electrodes (S, D, G)
- horizontal *field-effect*



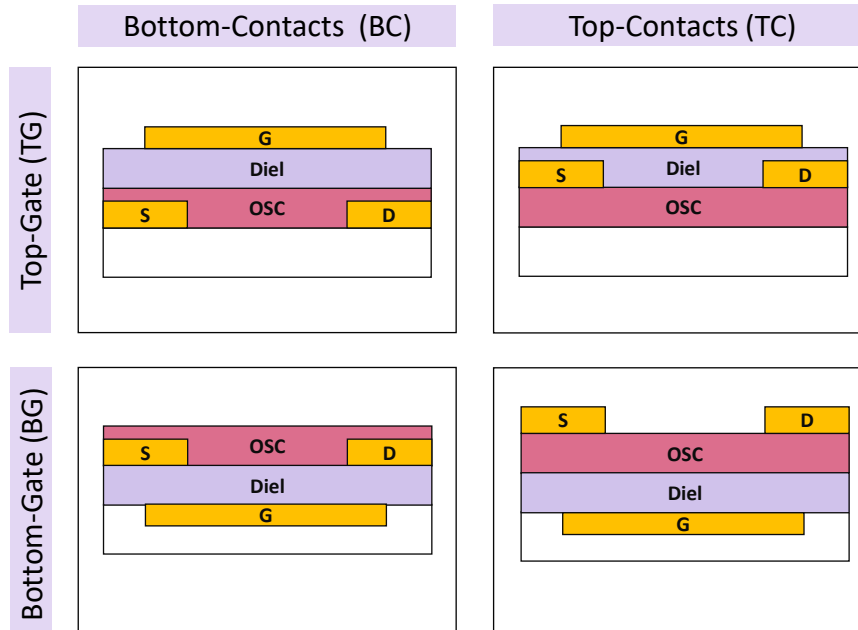
$$I_{D,lin} = \frac{W}{L} \mu C_i (V_G - V_{th}) V_D$$



$$I_{D,sat} = \frac{W}{2L} \mu C_i (V_G - V_{th})^2$$

OFET Configuration(s)

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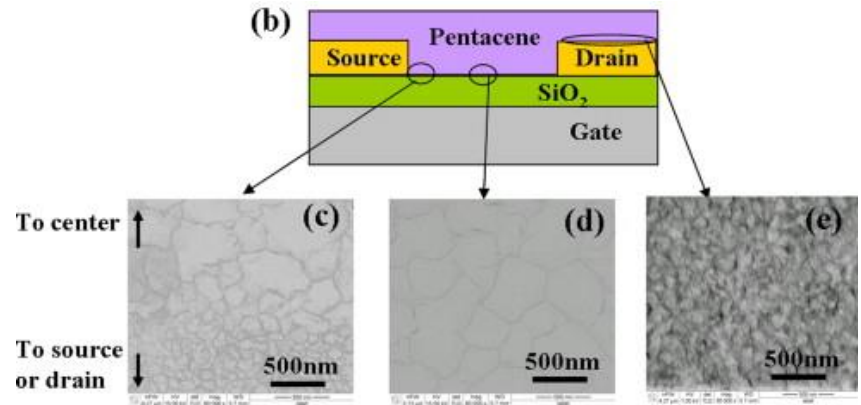
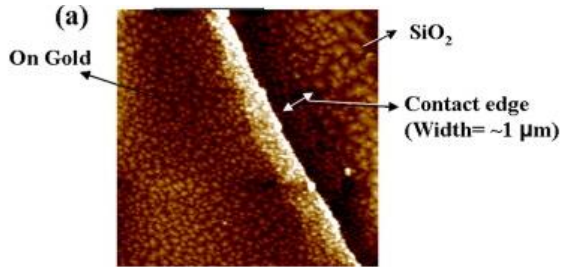


- is any fabrication process interfering/affecting OSC properties (*i.e.* electrode fabrication)?
- **OSC packing and film parameters** (*i.e.* mobility) depends on the underlying surface
- **interface(s) become crucial**

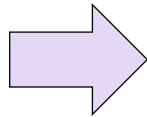
OFET: Top vs. Bottom Contacts

5

underlying surface/substrate



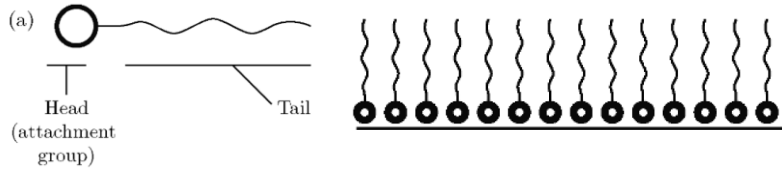
Org. El. 10(5), 775 (2009)



Contact resistance also changes based on underlying growth surface and the electrode

OFET: Improving Contacts with SAM

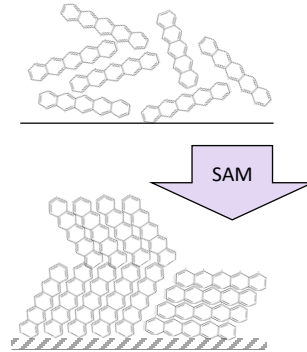
Self-Assembled Monolayer (SAM) can be used to improve (bottom) contacts, while enhancing adhesion and/or affinity



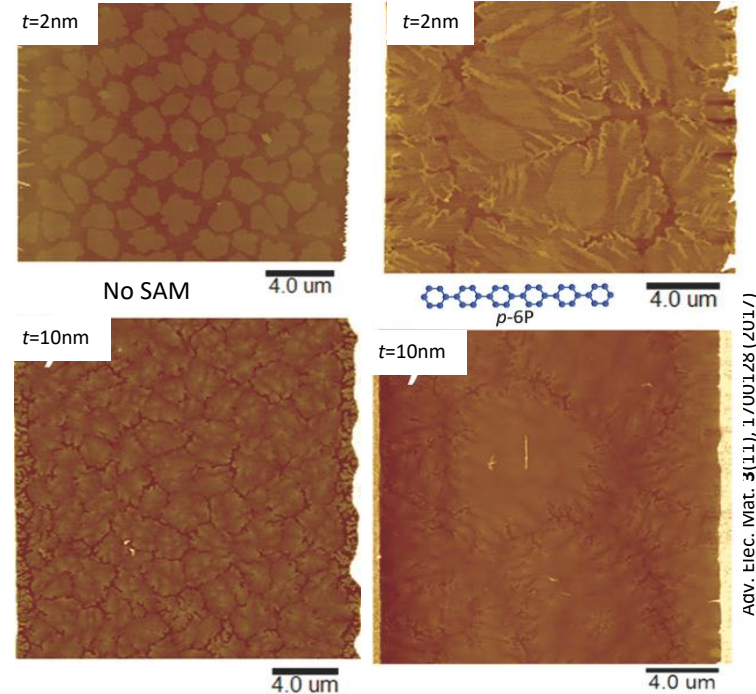
thiols attach to Au, Pt and other metals and creates low-surface energy layer on electrodes (thin enough to allow tunneling)

SAM can be selective:

- attachment selectivity
- cross-linking
- hydrophobic/hydrophilic nature
- amine termination
- fluorination
- selective tail reactivity



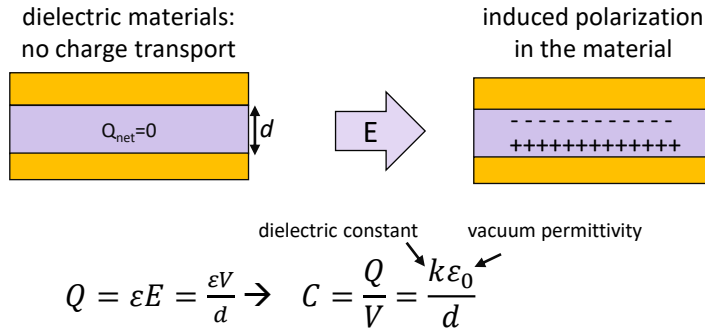
pentacene on Au surface



Different morphology of pentacene depending on the presence of SAM (*p*-6P) on underlying surface

OFET: Gate Dielectric

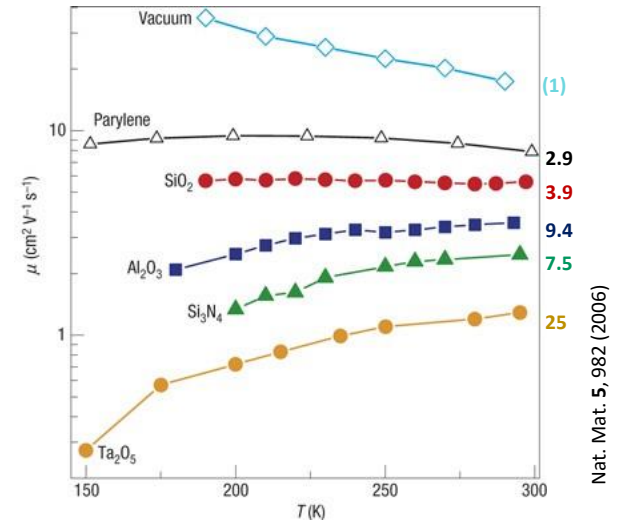
Charge redistribution at the dielectric surface can affect the properties of adjacent materials (electronic states and transport)



Carrier mobility depends on **device features** and **OSC/diel** interface:

- W, L, dielectric geometry and properties (C_i)
- conduction regime (linear and/or saturation)

V_{th} strongly depends **dielectric/OSC interface** due to **impurities** and **charge trapping sites** tend to increase this value. V_{th} can be modulated through value of C (tuning charge density at interface)

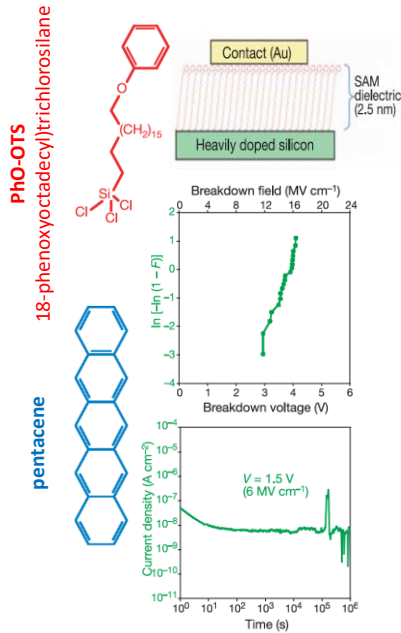


Temperature dependence of the mobility in single-crystal rubrene FETs with six different gate dielectrics (@ $V_G \sim -15$ V)

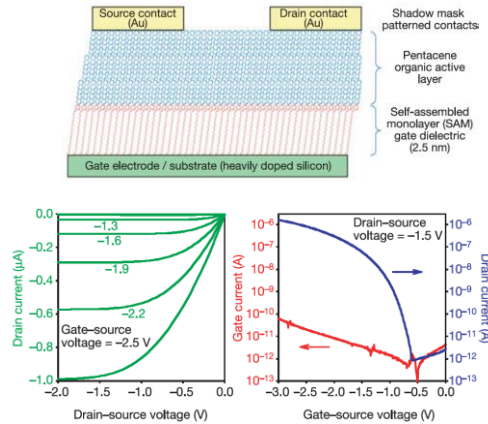
OFET: SAM as Gate Dielectrics

SAM: ultimate thinnest gate dielectric with high capacitance and low leakage current

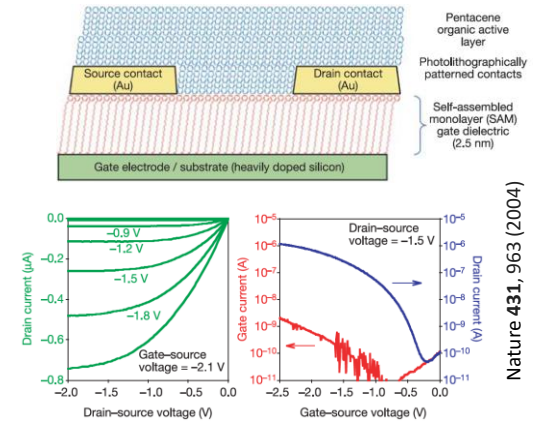
capacitor MIS structure



OFET structure (BG-TC)



OFET structure (BG-BC)

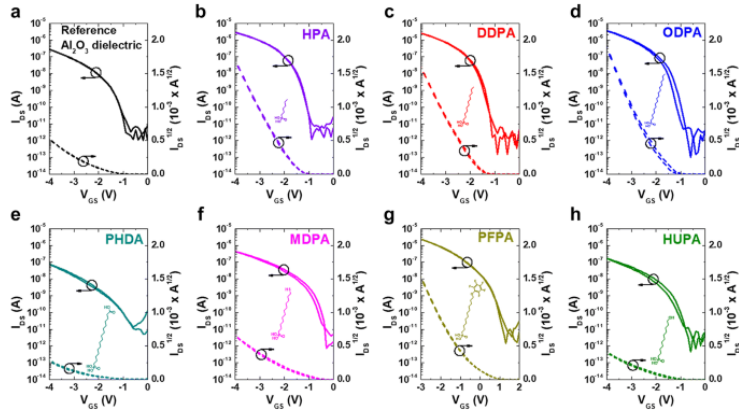
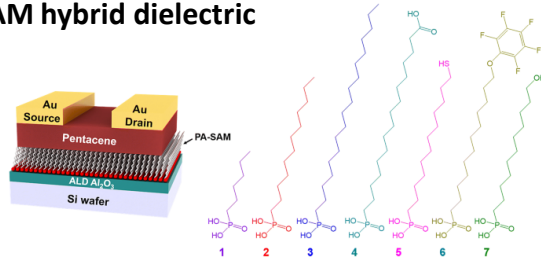


Schematics and electrical characterization of (left) capacitor-like structure and (middle) BG-TC and (right) BG-BC pentacene-based OFETs using PhO-OTS as dielectric layer.

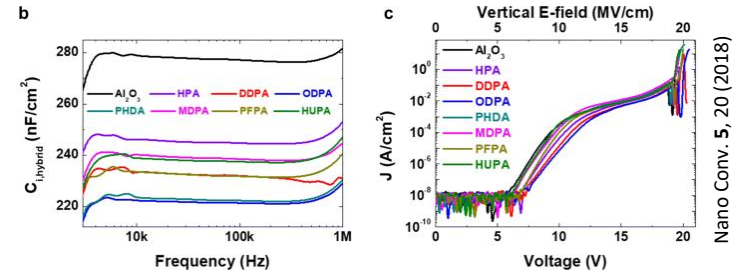
Nature 431, 963 (2004)

OFET: Hybrid SAM/Oxide Gate Dielectrics

Al₂O₃/SAM hybrid dielectric



Transfer characteristics (solid) and $\sqrt{I_{DS}}$ (dashed) of OFETs with hybrid dielectrics with various PA-SAMs (as labelled)

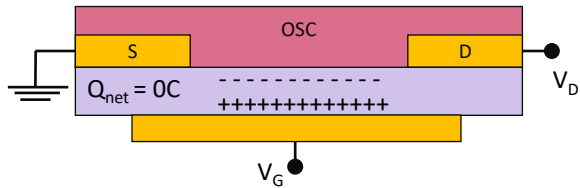


b. capacitive densities–frequency (C_f – f) and c. leakage current densities–voltage (J – V) of hybrid dielectrics with various PA-SAMs

Dielectric	Contact angle (°)	μ_{sat} (cm ² /Vs)	V_{Th} (V)	I_{on}/I_{off}
Al ₂ O ₃	< 10	0.05	– 2.18	~ 10 ⁵
HPA	102	0.35	– 1.71	~ 10 ⁶
DDPA	105.5	0.41	– 1.83	~ 10 ⁶
ODPA	109.8	0.58	– 1.84	~ 10 ⁶
PHDA	25.9	0.02	– 2.35	~ 10 ⁴
MDPA	65.1	0.05	– 1.64	~ 10 ⁵
PFFPA	102	0.27	– 0.58	~ 10 ⁶
HUPA	28.5	0.03	– 1.95	~ 10 ⁵

Al₂O₃ → high-k dielectric
SAM → favor interface with OSC

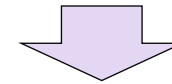
OFET: Gate Leakage



For an ideal (gate) dielectric, $I_G = 0A$ for any applied bias (V_D, V_G)

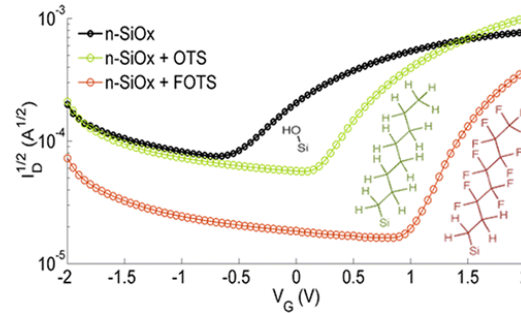
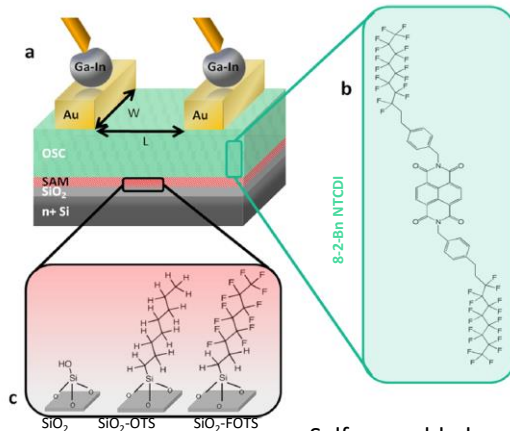
conservation of charge
 $I_D + I_S + I_G = 0$

ideal OFET ($I_G = 0$)
 $I_D = -I_S$



leakage current

- imperfect gate dielectrics
- surface conduction
- bulk device transport
- no OSC patterning

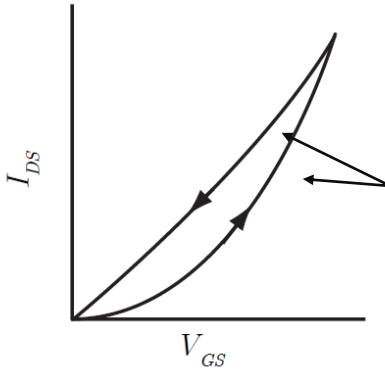


ACS Appl. Mat. & Int. 5, 7025 (2013)

Self-assembled monolayer dipole as an electrostatic barrier to reduce leakage currents in n-channel OFETs on SiO₂ dielectrics

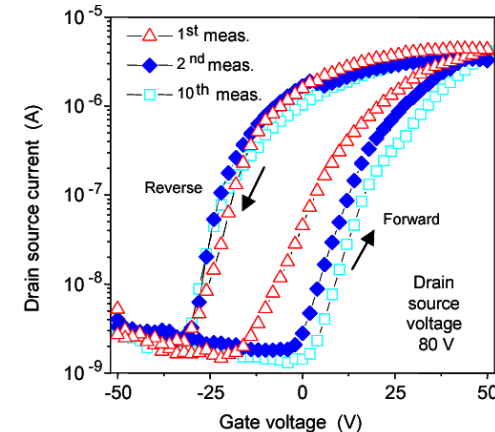
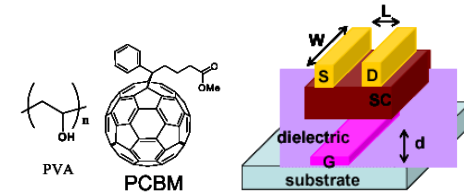
OFET: Hysteresis

Hysteresis appears when **gate voltage sweeps result in shift** (left or right) of the transfer characteristic, with subsequent change of the device V_{th}



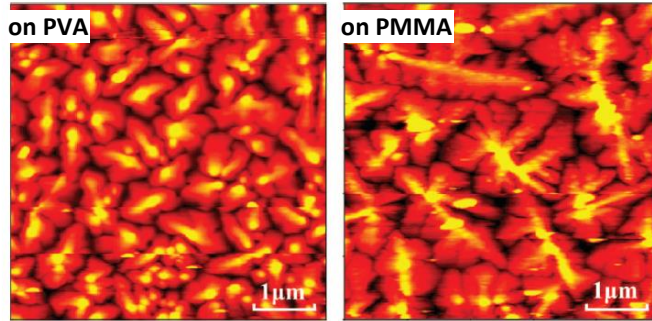
difference in charge distribution (and thus device properties), given the same bias condition

- **dielectric charge storage** injection of charge in the dielectric reduces the field felt by the OSC
- **water incorporation** in the gate dielectric (*i.e.* polymer dielectric with strong polar group), which leads to *slow dielectric relaxation*
- **traps** in the OSC can decrease/increase I_D ; traps are often *extrinsic* (*i.e.* water, oxygen) and this process can be reversible

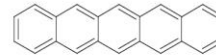


IEEE Trans. on Diel. and Elect. Insul. **13**(5), 1082 (2006)

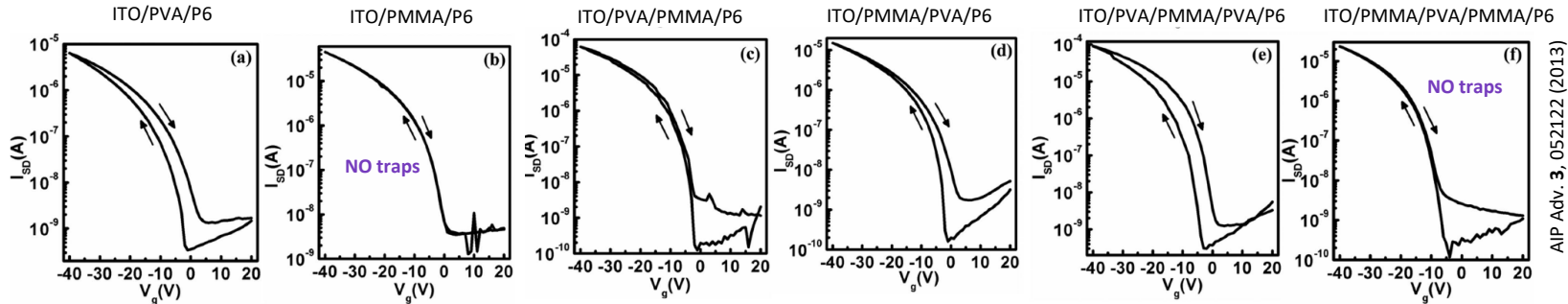
OFET: Reducing Hysteresis



Pentacene, P6 (50nm)



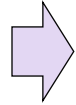
- charges from pentacene are trapped at the PVA/pentacene interface and PVA bulk
- charge (from gate) are trapped at PVA/gate interface and PVA bulk



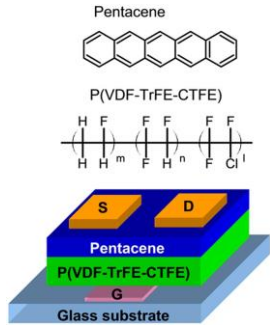
sandwich structure (PMMA/PVA/PMMA) allows controlling hysteresis in 0-10V range

OFET: *Exploiting* Hysteresis

Hysteresis is **NOT ALWAYS** **DETRIMENTAL** (if controllable)

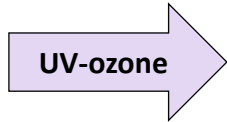
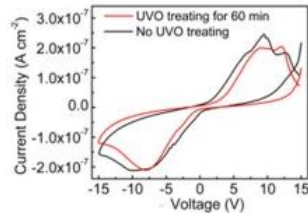
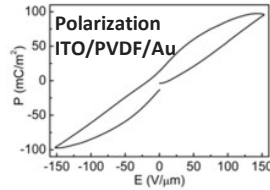


memory devices: modulation of channel conductance by remnant polarization of dielectrics after programming (P)/erasing (E) bias

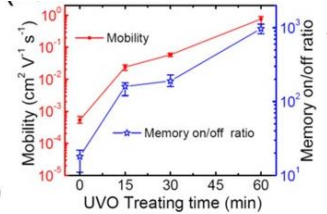
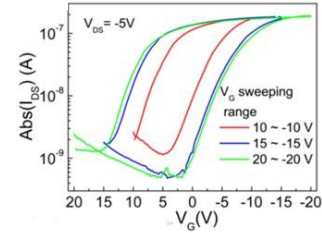


ferroelectric P(VDF-TrFE-CTFE)

- high dielectric constant
- remnant polarization (P_r) of 12.9 mC/m^2 @ 150 MV/m
- low coercive field $\sim 14 \text{ V}/\mu\text{m}$



modifies surface
→ pentacene with different grain size



- high mobility of $0.8 \text{ cm}^2/\text{Vs}$, low P/E voltage of $\pm 15 \text{ V}$
- large memory window (ΔV_T) of $15.4 \sim 19.2 \text{ V}$
- good memory ON/OFF ratio $\sim 10^3$
- endurance over 100 cycles, stable retention ability

Sci. Rep. 6, 36291 (2016)

Summary

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Today's Class

- ***Building blocks*** and **characteristics** of ***OFET*** (electrodes, dielectric, hysteresis)

Next

- ***Applications*** of organic field-effect transistors

